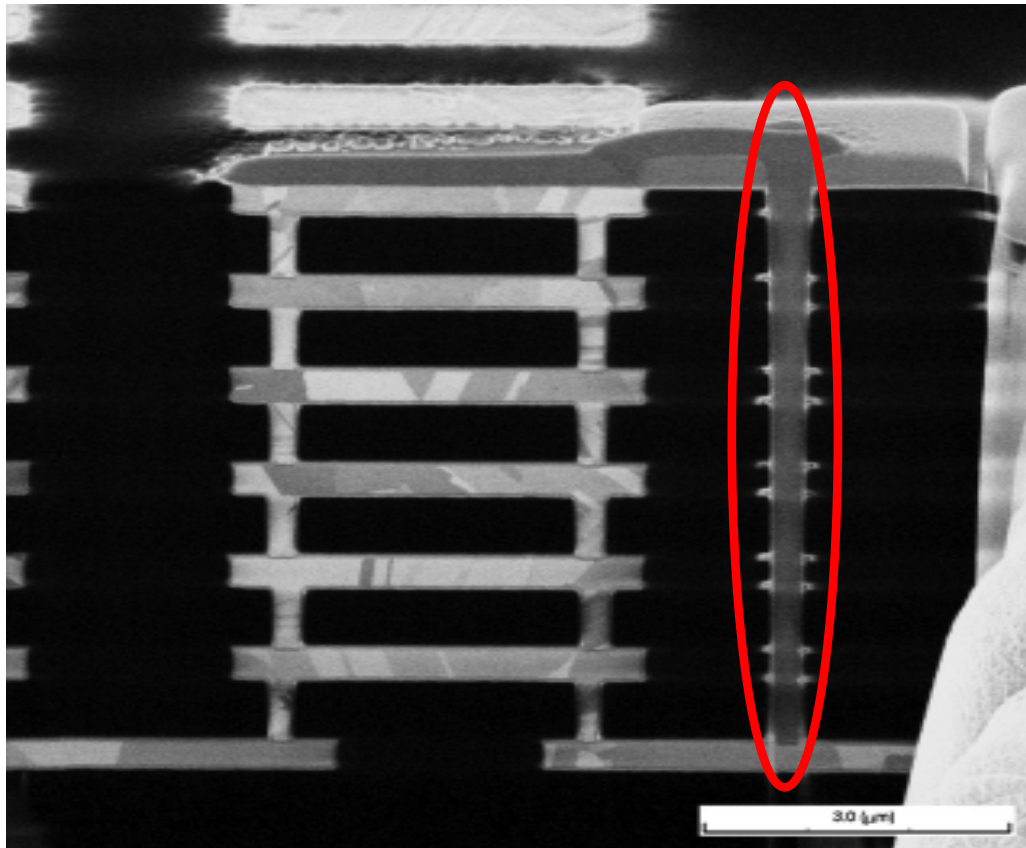


SII NanoTechnology Inc.
FIB Application

Multi-Gas Supply System Application

High aspect processing with assist gas

Application example of rewiring



Milling a hole on M1 of 7 layers, and filling by W deposition

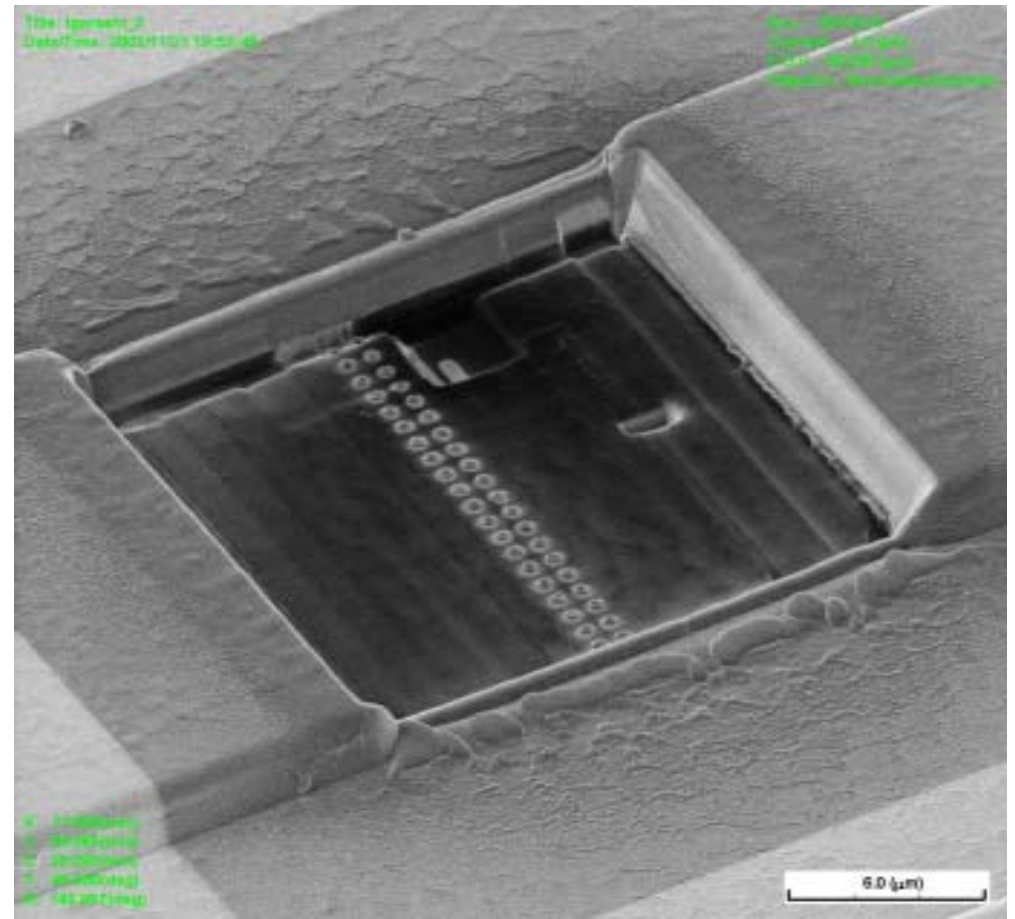
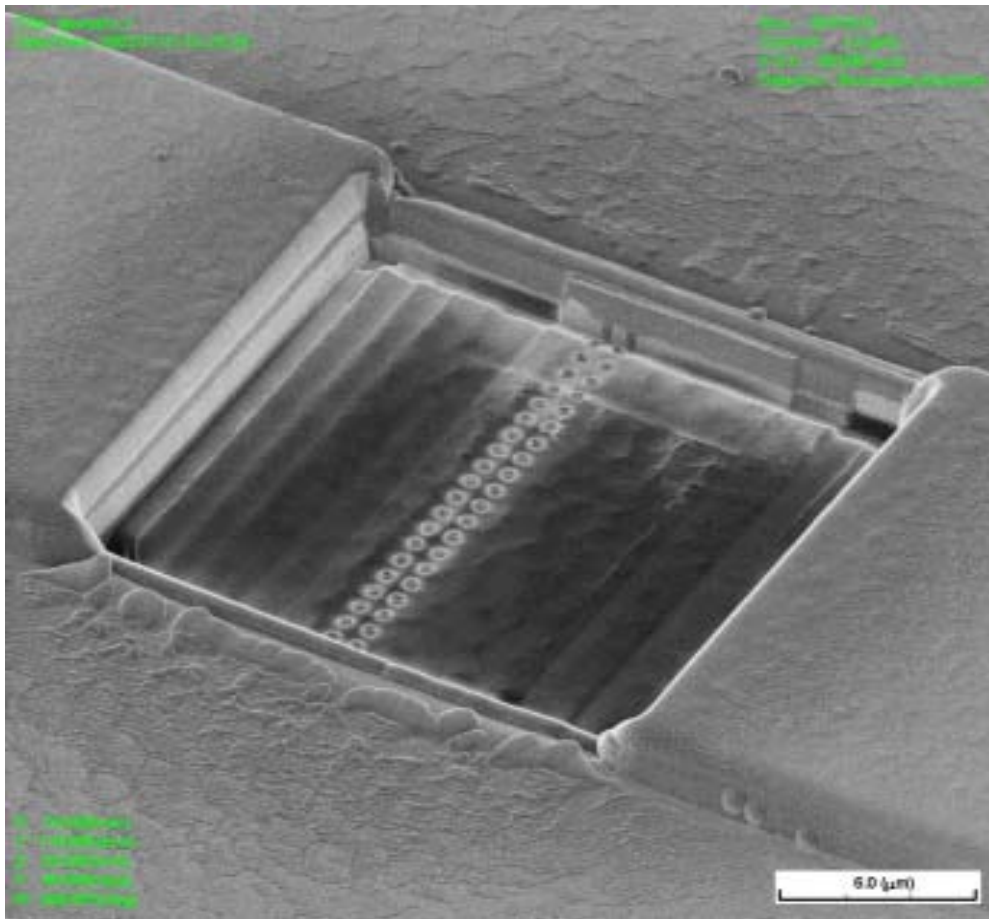
Assist gas : XeF_2

Opening: $0.5\mu\text{m}$, Depth: $7.5\mu\text{m}$

Aspect ratio : 15

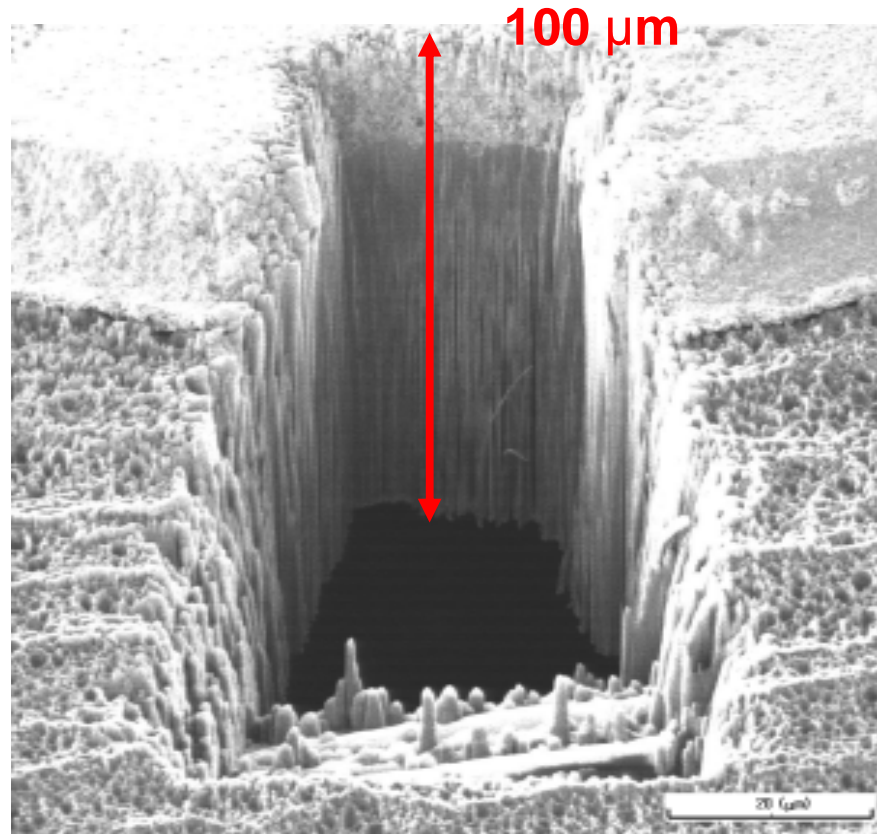
High aspect processing is enabled with use of assist gas

Rewiring with Gas Assist



Drilling of 5-layer wiring for repair

Example of large area processing
(cross sectional processing of 100 μm in depth)



Glass Epoxy Resin